

San Diego Convention Center
San Diego, California, USA

Advances in Metrology for X-Ray and EUV Optics VI (OP314)

Conference Chairs: **Lahsen Assoufid**, Argonne National Lab. (USA); **Haruhiko Ohashi**, Japan Synchrotron Radiation Research Institute (Japan); **Anand Krishna Asundi**, Nanyang Technological Univ. (Singapore)

Program Committee: **Simon G. Alcock**, Diamond Light Source Ltd. (United Kingdom); **Raymond Barrett**, European Synchrotron Radiation Facility (France); **Daniele Cocco**, SLAC National Accelerator Lab. (USA); **Ralf D. Geckeler**, Physikalisch-Technische Bundesanstalt (Germany); **Kenneth A. Goldberg**, Lawrence Berkeley National Lab. (USA); **Mikhail V. Gubarev**, NASA Marshall Space Flight Ctr. (USA); **Mourad Idir**, Brookhaven National Lab. (USA); **Weiguo Liu**, Xi'an Univ. of Technology (China); **Hidekazu Mimura**, The Univ. of Tokyo (Japan); **Josep Nicolas**, CELLS - ALBA (Spain); **Lorenzo Raimondi**, Elettra-Sincrotrone Trieste S.C.p.A. (Italy); **Rajdeep Singh Rawat**, National Institute of Education (Singapore); **Mark D. Roper**, Daresbury Lab. (United Kingdom); **Kawal Sawhney**, Diamond Light Source Ltd. (United Kingdom); **Frank Siewert**, Helmholtz-Zentrum Berlin für Materialien und Energie GmbH (Germany); **Regina Soufli**, Lawrence Livermore National Lab. (USA); **Peter Z. Takacs**, Brookhaven National Lab. (USA); **Muriel Thomasset**, Synchrotron SOLEIL (France); **Amparo Vivo**, European Synchrotron Radiation Facility (France); **Zhanshan Wang**, Tongji Univ. (China); **Kazuto Yamauchi**, Osaka Univ. (Japan); **Tanfer Yandayan**, TUBITAK UME (Turkey); **Valeriy V. Yashchuk**, Lawrence Berkeley National Lab. (USA); **Brian W. Yates**, Canadian Light Source Inc. (Canada)

This conference will address the broad issues in the growing and very demanding field of surface metrology and characterization of optics for EUV/X-Ray synchrotron and FEL radiation and for other EUV/X-Ray applications such as astronomical imaging, solar physics, and lithography. Improving the performance of existing instrumentation and techniques, as well as developing new and novel ones, is critical for the fabrication of high-quality optics to meet current and future requirements for these applications.

Papers are solicited on the following and related topics:

- surface figure and finish measurement
- slope profilometry and interferometry
- sub-aperture stitching
- wavefront sensing and characterization
- at-wavelength metrology of x-ray and EUV optics
- metrology of x-ray astronomy optics
- metrology of coherence-preserving mirrors
- metrology data analysis software and error reduction
- metrology of adaptive optics
- mirror characterization using scattering techniques
- mirror specification and tolerancing
- novel instrumentation and techniques
- mirror performance simulation using metrology data calibration tools and methods.

DATES

Conferences & Courses:
28 August - 1 September 2016

EXHIBITION

30 August - 1 September 2016

IMPORTANT DATES

Abstracts Due:

8 FEBRUARY 2016

Author Notification:

25 APRIL 2016

Manuscripts Due:

1 AUGUST 2016

Please Note: Submissions imply the intent of at least one author to register, attend the conference, present the paper as scheduled, and submit a full-length manuscript for publication in the conference proceedings.

By submitting an abstract, I agree to the following conditions:

AN AUTHOR OR COAUTHOR (INCLUDING KEYNOTE, INVITED, ORAL, AND POSTER PRESENTERS) WILL:

- Register at the reduced author registration rate (current SPIE Members receive an additional discount on the registration fee).
- Attend the meeting.
- Make the presentation as scheduled in the program.
- Submit a manuscript (6 pages minimum, 20 pages maximum) for publication in Proceedings of SPIE in the SPIE Digital Library.
- Obtain funding for registration fees, travel, and accommodations, independent of SPIE, through their sponsoring organizations.
- Ensure that all clearances, including government and company clearance, have been obtained to present and publish. If you are a DoD contractor in the USA, allow at least 60 days for clearance.

Submit an abstract and summary online at:

<http://spie.org/opticalcall>:

- Once you choose a conference, click “Submit an abstract” from the conference call for papers.
- Please submit a 250-word text abstract for technical review purposes that is suitable for publication. SPIE is authorized to circulate your abstract to conference committee members for review and selection purposes.
- Please also submit a 100-word text summary suitable for early release. If accepted, this summary text will be published prior to the meeting in the online or printed programs promoting the conference.
- To provide the research community with enhanced access to information presented at SPIE conferences, SPIE will record the audio plus screen content of oral presentations and, with author permission only, will publish the recordings on the SPIE Digital Library. When submitting an abstract, you will be asked to respond to the permission request.
- Only original material should be submitted.
- Abstracts should contain enough detail to clearly convey the approach and the results of the research.
- Commercial papers, papers with no new research/development content, and papers where supporting data or a technical description cannot be given for proprietary reasons will not be accepted for presentation in this conference.
- Please do not submit the same, or similar, abstracts to multiple conferences.

REVIEW, NOTIFICATION, AND PROGRAM PLACEMENT INFORMATION

- To ensure a high-quality conference, all submissions will be assessed by the Conference Chair/Editor for technical merit and suitability of content.
- Conference Chair/Editors reserve the right to reject for presentation any paper that does not meet content or presentation expectations.
- The contact author will receive notification of acceptance and presentation details by e-mail the week of 25 April 2016.
- Final placement in an oral or poster session is subject to the Chairs' discretion.

PROCEEDINGS OF SPIE AND SPIE DIGITAL LIBRARY INFORMATION

- Manuscript instructions are available from the “For Authors/Presenters” link on the conference website.
- Conference Chair/Editors may require manuscript revision before approving publication and reserve the right to reject for publication any paper that does not meet acceptable standards for a scientific publication. Conference Chair/Editors' decisions on whether to allow publication of a manuscript is final.
- Authors must be authorized to transfer copyright of the manuscript to SPIE, or provide a suitable publication license.
- Only papers presented at the conference and received according to publication guidelines and timelines will be published in the conference Proceedings of SPIE in the SPIE Digital Library.
- Published papers are indexed in leading scientific databases including Astrophysical Data System (ADS), Chemical Abstracts (relevant content), Compendex, CrossRef, Current Contents, DeepDyve, Google Scholar, Inspec, Portico, Scopus, SPIN, and Web of Science Conference Proceedings Citation Index, and are searchable in the SPIE Digital Library. Full manuscripts are available to SPIE Digital Library subscribers worldwide.